

Docket No.: 055071-0329



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
Doug van den BROEKE, et al.	:	Confirmation Number: 3769
Application No.: 10/756,830	:	Group Art Unit: 2891
Filed: January 14, 2004	:	Examiner: EVERHART, CARIDAD
For: METHOD AND APPARATUS FOR PROVIDING OPTICAL PROXIMITY FEATURES TO A RETICLE PATTERN FOR DEEP SUB-WAVELENGTH OPTICAL LITHOGRAPHY		

INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

03/03/2006 HALI11 00000103 500417 10756830

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In accordance with 37 CFR 1.17(p), please charge the fee of **\$180.00** to Deposit Account No. 500417.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0329SERIAL NO.
10/756,830APPLICANT
Doug van den BROEKE, et al.FILING DATE
January 14, 2004GROUP
2891

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		US 5,895,741	04-20-1999	Hasegawa et al.	
		US 6,214,497 B1	04-10-2001	Stanton	
		US 2002/0152452 A1	10-17-2002	Socha	
		US 5,682,323	10-28-1997	Pasch et al.	
		US 6,303,253 B1	10-16-2001	Lu	
		US 6,223,139 B1	04-24-2001	Wong et al.	
		US			
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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		EP 1 202 119 A1	05-02-2002	ASML Masktools B.V.		x	
		WO 03/054626 A1	07-03-2003	ADVANCED MICRO DEVICES, INC.		x	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," Optical Microlithography XIII, Proceedings of SPIE, 2000, pp 1156-1162, Vol. 4000
		Kyoji NAKAJO, et al., "Auxiliary pattern generation to cancel unexpected images at sidelobe overlap regions in attenuated phase-shift masks,"
		Nicolas Bailey COBB, "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing," Ph.D. dissertation, Spring 1998, pp 35-72, University of California at Berkeley
		J. Fung CHEN, et al., "Practical I-Line OPC Contact Masks for Sub-0.3Micron Design Rule Application: Part 1—OPC Design Optimization," pp 181-201
		J.A. TORRES, et al., "Contrast-Based Assist Feature Optimization," Optical Microlithography XV, 2002, pp 179-187, Proceedings of SPIE, Vol 4691, SPIE
		Olivier TOUBLAN, et al., "Fully Automatic Side Lobe Detection and Correction Technique for Attenuated Phase Shift Masks," Optical Microlithography XIV, 2001, pp 1541-1547, Proceedings of SPIE, Vol. 4346, SPIE
		Michael S. YEUNG, "Extension of the Hopkins theory of partially coherent imaging to include thin-film interference effects," Optical/Laser Microlithography VI, 1993, pp 452-463, SPIE, Vol. 1927
		Douglas VAN DEN BROEKE, et al., "Near 0.3 μ m Full Pitch Range Contact Hole Patterning Using Chromeless Phase Lithography (CPL)," Proceedings of the SPIE, September 9, 2003, pp 297-308, Vol. 5256, SPIE

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.